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INFORMATION DISCLOSURE July 13, 2001 Filing Date STATEMENT BY APPLICANT **First Named Inventor** Dyks Jerald P. Group Art Unit 2881 (use as many sheets as necessary) **Examiner Name** 11460-111 Attorney Docket Number Sheet of

				U.S. PATENT DOC	UMENTS	
Examiner Initials	Cite No.1	Number (if kn	Code ²	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
W		5,814,194		Deguchi et al.	09/29/1998	
IN		6,207,282BI		Deguchi et al.	03/27/2001	
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Date Examiner Considered Signature

*EXAMINER: Initial if reference considered, whether not ditation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). 4 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. Skind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.





FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO.: 11460-111

APPLICATION SERIAL NO.: 09/905,536

GROUP ART UNIT: 2881

APPLICANT: Jerald P. Dykstra

EXAMINER: N/A

FILING DATE: July 13, 2001

CONFIRMATION NO.: 3492

U.S. PATENT DOCKETS

EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS/SUB- CLASS	FILING DATE IF APPROPRIATE
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LN	5,459,326	10/17/95	Yamada	250/398	01/09/95
11/	5,185,287	02/09/93	Aoyagi et al.	437/105	01/15/91
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EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS/SUB- CLASS	TRANSLATION YES NO
LN	JP 03245523A	11/01/91	Aoyanagi et al.		Abstract only
LN	JP 62112777 A1	11/11/85	Aoki		Abstract only
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3.	N. Toyoda et al., "Cluster Size Measurement of Large Ar Cluster Ions with Time of
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EXAMINER	announ	DATE CONSIDERED
		03/21/2003